



SDI Review Form 1.6

Journal Name:	American Chemical Science Journal
Manuscript Number:	Ms_ACSJ_23356
Title of the Manuscript:	Chemical bath deposition of ZnSe thin films: Investigations of the growth conditions
Type of the Article	Original Research paper

General guideline for Peer Review process:

This journal's peer review policy states that **NO** manuscript should be rejected only on the basis of '**lack of Novelty**', provided the manuscript is scientifically robust and technically sound.

To know the complete guideline for Peer Review process, reviewers are requested to visit this link:

(<http://www.sciencedomain.org/page.php?id=sdi-general-editorial-policy#Peer-Review-Guideline>)



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PART 1: Review Comments

	Reviewer's comment	Author's comment (if agreed with reviewer, correct the manuscript and highlight that part in the manuscript. It is mandatory that authors should write his/her feedback here)
Compulsory REVISION comments		
Minor REVISION comments	Results and discussion part of the article should be improved by giving more references from the previous studies.	I have added some literature reviews regarding the band gap energies of ZnSe films. 1. Al-Kuhaili MF, Kayani A, Durrani SMA, Bakhtiari IA, Haider MB. Band gap engineering of zinc selenide thin films through alloying with cadmium telluride. ACS Appl. Mater. Interfaces. 2013; 5: 5366-5372. 2. Ezema FI, Ekwealor ABC, Osuji RU. Effect of thermal annealing on the band gap and optical properties of chemical bath deposited ZnSe thin films. Turk. J. Phys. 2006; 30: 157-163. 3. Lokhande CD, Patil PS, Tributsch H, Ennaoui A. ZnSe thin films by chemical bath deposition method. Sol. Energy Mater. Sol. Cells. 1998; 55: 379-393. 4. Kale RB, Lokhande CD. Influence of air annealing on the structural, morphological, optical and electrical properties of chemically deposited ZnSe thin films. Appl. Surf. Sci. 2005; 252: 929-938. 5. Kale RB, Lokhande CD. Room temperature deposition of ZnSe thin films by successive ionic layer adsorption and reaction (SILAR) method. Mater. Res. Bull. 2004; 39: 1829-1839.
Optional/General comments		